

Thin and Edgeless silicon planar pixel sensors

For ATLAS inner tracker upgrade

A. Ducourthial¹, A. Bagolini², M. Bomben¹, M. Boscardin², L. Bosisio³, G. Calderini¹, L. D'Eramo¹, G-F. Dalla Betta², G. Darbo², G. Giacomini^{2,4}, I. Luise¹, G. Marchiori¹, M. Meschini², A. Messineo², S. Ronchin², N. Zorzi²

1 Laboratoire de Physique Nucléaire et de Hautes Énergies (LPNHE), 75005 Paris, France

2 Fondazione Bruno Kessler, Centro per i Materiali e i Microsistemi (FBK-CMM), I-38123 Povo di Trento (TN), Italy

3 Università di Trieste, Dipartimento di Fisica and INFN, I-34127 Trieste, Italy

4 Brookhaven National Laboratory, Instrumentation Division 535B, Upton, NY - USA

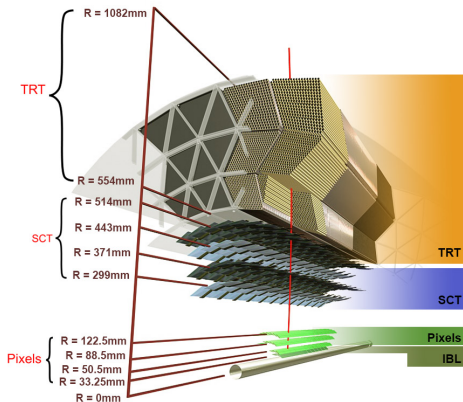


Table of contents

1. Introduction: ATLAS Inner Tracker Upgrade
2. LPNHE-FBK-INFN sensors
3. Testbeam results: Active edge sensors, not irradiated
4. Testbeam results: Thin irradiated sensors

Introduction: ATLAS Inner Tracker Upgrade

ATLAS Tracker



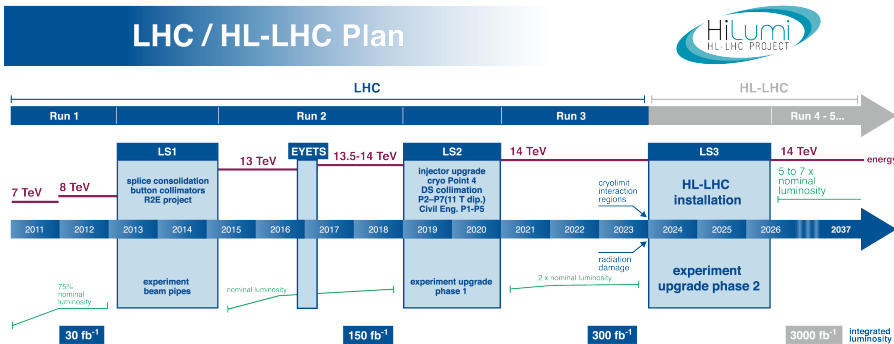
- ▶ 3 subdetectors: Pixels, SCT, TRT
- ▶ Pixel detectors composed of now 4 barrel layers (IBL)
- ▶ η acceptance: $-2.5 < \eta < 2.5$
- ▶ Excellent performances in terms of spatial resolution and hit efficiency, but
- ▶ Expected fluence at the end of lifetime: 1 and 5 $\times 10^{15} n_{eq}/cm^2$

$$\eta \equiv -\ln \left[\tan \left(\frac{\theta}{2} \right) \right]$$

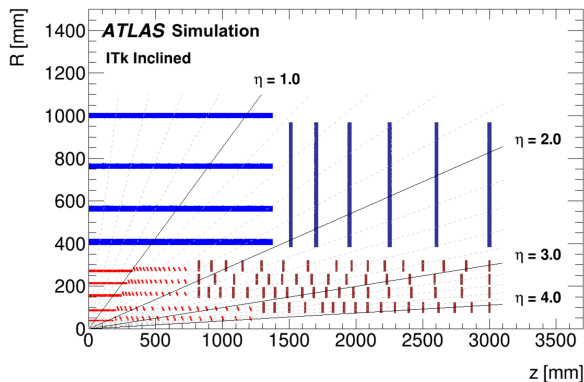
ATLAS Upgrade

ATLAS data taking phase in HL LHC conditions (start in 2026):

- ▶ Peak luminosity of $L_{inst} \simeq 7.5 \times 10^{34} \text{cm}^{-2}\text{s}^{-1}$
- ▶ 200 inelastic pp collisions per bunch crossing
- ▶ By the end of 2037, ATLAS will collect 3000 fb^{-1} (4000 fb^{-1} ?)
- ▶ Fluence inner tracker $2 \times 10^{16} n_{eq}/\text{cm}^2$ (4 times IBL fluence)



ATLAS Inner Tracker Upgrade (ITK) Layout



pixels (red) - strips
(blue)

Pixel options:

- ▶ 3D silicon pixels
- ▶ Planar silicon pixels
- ▶ CMOS pixels

Pixel TDR due for end of 2017:

- * All silicon tracker
- * 10 m^2 of pixels more than 600 Millions electronic channels
- * 200 m^2 of strips

ITK Pixels Challenges

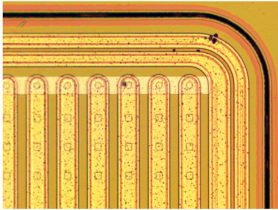
ITK major challenges:

- ▶ **Radiation hardness:** Retain a 97% efficiency with a fluence up to $2 \times 10^{16} n_{eq}/cm^2$ for innermost layer
 - * Thinner sensors to fight charge trapping
 - * Rad harder 3D sensors for innermost layer (cf Cinzia's talk)
 - * LPNHE 130 μm thick sensors irradiated at $1 \times 10^{16} n_{eq}/cm^2$, our R&D focuses on planar sensors for intermediate layers
- ▶ **High event rate and pile up compliance:**
 - * Granularity ($50\mu m \times 50\mu m$ or $25\mu m \times 100\mu m$ pitch instead of $250\mu m \times 50\mu m$)
 - * New chip RD53 $50 \times 50\mu m$ to deal with high data rate at HL-LHC
- ▶ **Increase the geometrical acceptance**
 - * Instrument at high eta, cf Inclined layout
 - * Reduction of dead area \Rightarrow LPNHE Active edge sensors

LPNHE-FBK-INFN sensors

PRODUCTION 1 & 2

Active edge sensors



- ▶ N-on-P devices
- ▶ Pixel pitch: $50\ \mu\text{m}$ by $250\ \mu\text{m}^*$
- ▶ Temporary metal for biasing in initial sensor QA before bonding to FE

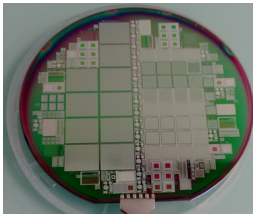
- ▶ Thickness: $200\ \mu\text{m}$

Active edge:

- ▶ Deep Reactive Ion Etching
- ▶ $100\ \mu\text{m}$ from last pixel; 0, 2 GRs

Development of Edgeless n-on-p Planar Pixel Sensors for future ATLAS Upgrades, M Bomben et al, Nucl. Instr. and Meth. A 2013:712:41-47

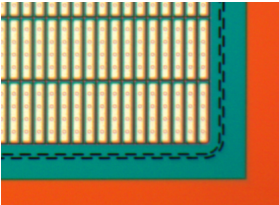
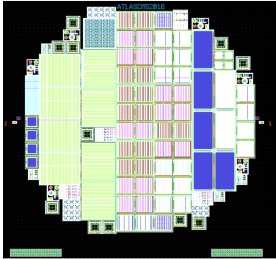
Thin sensors



- ▶ 6 inches SiSi wafers
- ▶ N-on-P devices
- ▶ Pixel pitch: $50\ \mu\text{m}$ by $250\ \mu\text{m}^*$
- ▶ Thickness: 100 and $130\ \mu\text{m}$

- ▶ Passivation against discharge: BCB
- ▶ 2 sensors irradiated up to a fluence of $1.1 \times 10^{16} n_{eq}/\text{cm}^2$

Production 3: Thin and Active edge sensors



FBK production: 4 FEI4b sensors

- ▶ SiSi wafers
- ▶ N-on-P devices
- ▶ thickness: 100 μm
- ▶ 2 FEI4 50 μm pixel to trench, 0 GRs
- ▶ 1 FEI4 75 μm pixel to trench, 0 GRs
- ▶ 1 FEI4 75 μm pixel to trench, 1 GR
- ▶ Segmented trench design

Also: 5 RD53 compatible sensors

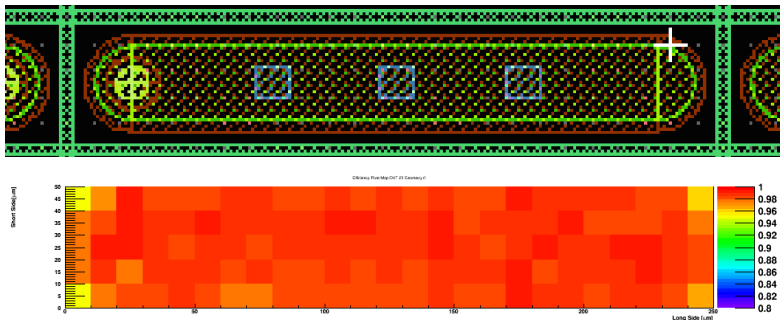
Status: Bump bonding at IZM (Berlin)

Testbeam results: Active edge
sensors, not irradiated

GLOBAL EFFICIENCY & IN PIXEL EFFICIENCY

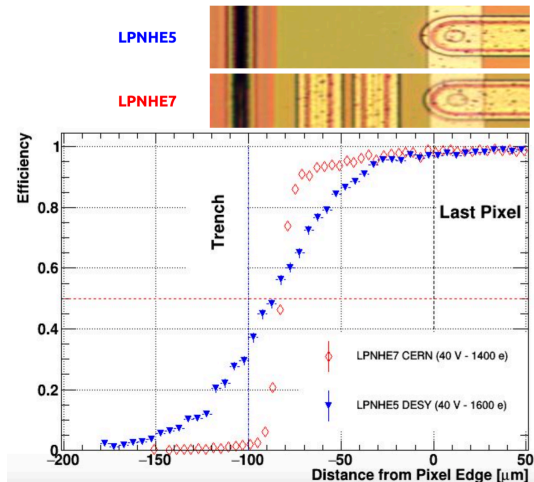
Global Efficiency: 98 % when biased at 40 V (depleted at 20V)

In Pixel efficiency:



Temporary metal line to bias sensors before bump bonding:
No permanent bias structures results in **uniform hit efficiency**

EDGE EFFICIENCY



LPNHE 5 (0 GR):

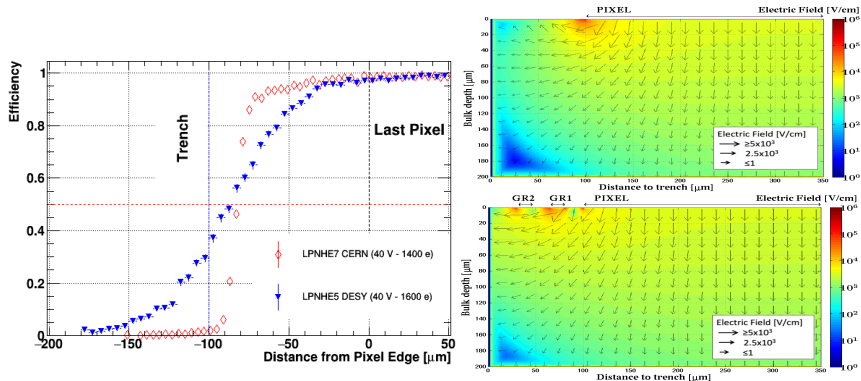
- Higher threshold 1600e
- Multiple scattering DESY

LPNHE 7 (2GR)

Efficiency higher than 50% up to 92 μm from the last pixel

⇒ GRs don't impact too severely on the hit-efficiency

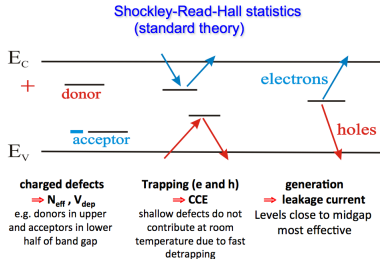
EDGE EFFICIENCY - COMPARISON WITH TCAD SIMULATION



- ▶ Charge is not collected and reemitted by GRs apart from few μm below the GR area
- ▶ Simulation TCAD supports the hypothesis
- ▶ **Uninstrumented area is no longer dead!**

Testbeam results: Thin irradiated
sensors

Intermezzo: Radiation damage in silicon

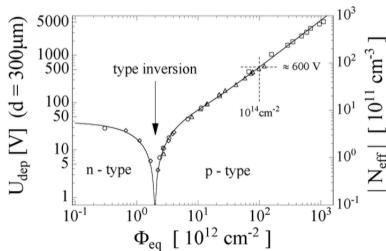


Radiation (NIEL) creates new energy states (deep defects) in the gap:

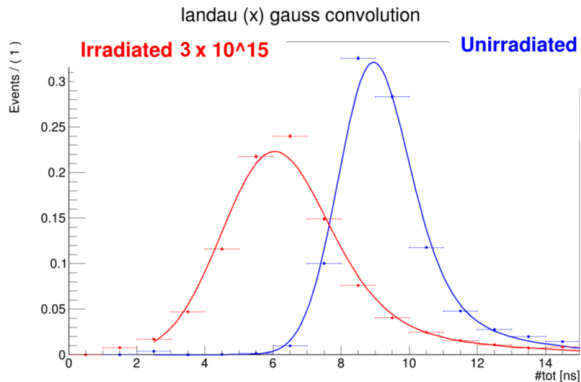
- Charge trapping
- Type inversion

Macroscopic effects:

1. ↘ Charge Collection efficiency
2. ↗ Leakage Current
3. ↗ Depletion Voltage



Charge collection at $3 \times 10^{15} n_{eq}/cm^2$



$V_{bias} = 600V$

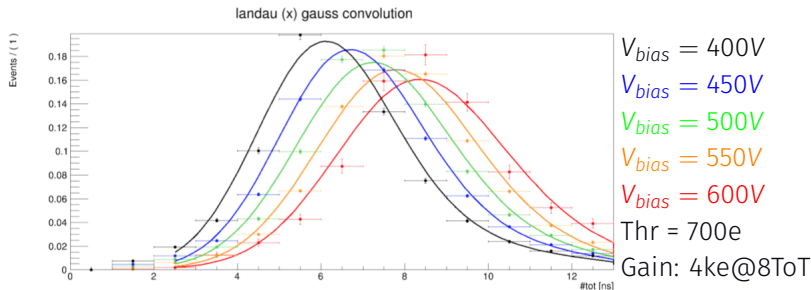
$V_{bias} = 100V$

Thr = 1ke

Gain: 6ke@6ToT

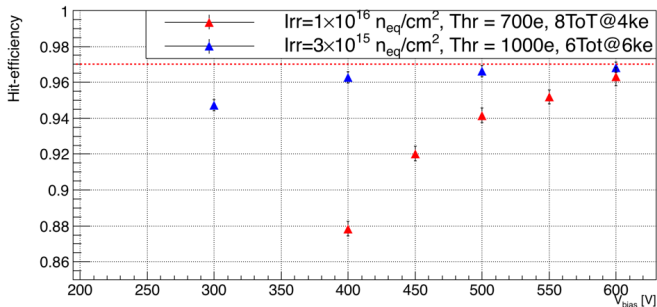
- ▶ Charge trapping: decrease of charge collection
- ▶ Irradiation of $130 \mu m$ thick sensor reduce the signal by 3 ToT units: $MPV_{irr} \simeq 6$ $MPV_{unirr} \simeq 9$
- ▶ At $3 \times 10^{15} n_{eq}/cm^2$, charge collection is reduced by $\simeq 33\%$ compared to unirradiated sensors.

Charge and bias voltage at $1 \times 10^{16} n_{eq}/cm^2$



- Evolution of the depletion with voltage for highly irradiated sensor: $1 \times 10^{16} n_{eq}/cm^2$
- At 600V, MPV $\simeq 8.5$ so induced charge close to 4000 e.
Degradation of charge collection efficiency of $\simeq 50\%$ compared to unirradiated sensor

Sensor efficiency vs bias voltage and fluence up to $1 \times 10^{16} n_{eq}/cm^2$



- ▶ At $1 \times 10^{16} n_{eq}/cm^2$ and 600V, efficiency is $96.32 \pm 0.5\%$, quite close to the 97% ATLAS requirement
- ▶ At $3 \times 10^{15} n_{eq}/cm^2$ and 600 V, efficiency reaches 97%

NB: Low threshold gives better results

CONCLUSIONS

- ▶ Thanks to the **Active edge** technology, the edge region is **efficient above 97% up to $70\mu m$ from last pixel**
- ▶ **Thin sensors highly efficient after irradiation:** $\simeq 96.5\%$ at $1 \times 10^{16} n_{eq}/cm^2$ and higher than 97 % at $3 \times 10^{15} n_{eq}/cm^2$
- ▶ Thanks to **temporary metal** no permanent biasing structures, so **very homogeneous efficiency** in the whole pixel cell

To be tested in beam in autumn 2017:

- ▶ Combination of thin and active edge sensors (production 3) soon to be delivered.

Acknowledgements

For Productions 2 and 3:

This work was supported by the Italian National Institute for Nuclear Physics (INFN), Projects ATLAS, CMS, RD-FASE2 (CSN1)

- ▶ Principal investigators: Marco Meschini, Gian Franco Dalla Betta, Maurizio Boscardin, Giovanni Darbo, Gabriele Giacomini, Sabina Ronchin, Alberto Messineo

and by AIDA-2020 Project EU-INFRA Proposal no. 654168.

The authors want to thank the CERN IRRAD team for helping with the irradiation of the detectors.



AIDA²⁰²⁰

